In the Claims

1. (Currently amended) Epitaxy equipment comprising:

an epitaxy chamber under vacuum containing a substrate support and at least one cell under vacuum for evaporation of epitaxy material closed by a diaphragm having at least one opening and communicating with the epitaxy chamber by a connecting flange, and

a mobile plate positioned opposite the diaphragm such that the distance of the plate from an exterior surface of the diaphragm is variable and has a <u>cross</u> section corresponding to a <u>cross</u> section of the diaphragm and a molecular beam is formed at the <u>a</u> level of a zone surrounding the plate.

- 2. (Original) The epitaxy equipment according to claim 1, wherein the plate is disc-shaped.
- 3. (Original) The epitaxy equipment according to claim 1, wherein the plate is mobile in a direction perpendicular to the diaphragm.
- 4. (Original) The epitaxy equipment according to claim 2, wherein the distance is 10 millimeters.
- 5. (Currently amended) The epitaxy Epitaxy equipment according to claim 1 comprising:

 an epitaxy chamber under vacuum containing a substrate support and at least one cell under vacuum for evaporation of epitaxy material closed by a diaphragm having at least one opening and communicating with the epitaxy chamber by a connecting flange,

an wherein the plate is angularly mobile plate positioned opposite the diaphragm such that the plate and forms a dihedron variable with a plane of the diaphragm, the distance of a center of the plate from an exterior surface of the diaphragm being variable,

the plate having a cross section corresponding to a cross section of the diaphragm, and a molecular beam being formed at a level of a zone surrounding the plate.

- 6. (Original) The epitaxy equipment according to claim 1, wherein the plate is made of metal or a dielectric material.
- 7. (Currently amended) The epitaxy equipment according to claim 1, wherein the plate is actuated by a connecting organ control rod traversing a wall of the epitaxy chamber via an airtight passage.
- 8. (Original) The epitaxy equipment according to claim 1, wherein the diaphragm has perforations.
- 9. (Original) The epitaxy equipment according to claim 1, wherein the diaphragm has an annular opening.